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(54) Title: PLANT-PATHOGEN RESISTANCE

(57) Abstract

The present invention provides a method of reducing the period within which a plant's natural defence mechanism responds to attack by a plant pathogen, the method comprising causing the plant to maintain in at least a part of the plant a level of BiP, or a homologue thereof, which is greater than the endogenous level for said plant in non-stressful conditions. The invention also provides for a modified plant produced by the method of the invention.

